



Real Time In Situ Gas Flow Monitoring Specified for New Etch Tool Purchases by Leading IDMs

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GAS FLOW MONITORING IS CRITICAL FOR NEW ETCH TOOLS

Pleasanton, CA.—June 30, 2010—Pivotal Systems Corporation, the leader in advanced process monitoring and control solutions, today announced that two leading logic IDMs have specified all new etch tool purchases would need to have real time in situ gas flow monitoring capability to an accuracy of $\pm 1\%$. The motivation for this specification is to combat yield excursions and improve chamber matching as they push into the 3X and 2X nanometer technology nodes.

“We are seeing a tremendous amount of concern on repeatability and accuracy of gas flow as IDMs move to more complex etch recipes that require short processing steps, low gas flow rates, and continuous plasma processing,” said Mukund Venkatesh, Vice President of Marketing at Pivotal, “As a result, IDMs are beginning to demand this capability from their etch tool vendors. There are a number of offline gas flow calibration solutions available on the market today, but Pivotal’s GFM system is the only one to offer real time in situ measurements—this is key because the IDMs are worried about the variations that happen from wafer to wafer during production versus the one time calibration efforts that can be made on a monthly or weekly basis.”

“With continuous plasma processing, MFC turn-on transients and the variations that occur from wafer to wafer are of big concern to us,” noted a senior etch process engineer at one of the IDMs, “A real time gas flow monitoring system like GFM can provide us with invaluable information as to how the MFC is performing during the first few seconds of turn on time for each and every processed wafer.”

“I believe we are seeing the tipping point where real time gas flow monitoring is required on all new tools,” said Cliff Neal, Pivotal’s Vice President of Global Sales, “Given how critical it is to the wafer processing results and how poorly it is controlled today relative to other parameters like pressure, temperature, and RF, adoption of real time gas flow monitoring is a no-brainer.”

About Pivotal Systems

Pivotal Systems Corporation provides best-in-class monitoring and process control technology for the semiconductor manufacturing industry. Pivotal’s vision is to enable an order of magnitude increase in fab productivity and capital efficiency for current and future technology nodes. This vision is achieved through its real time in situ process monitoring and control solutions. Founded in 2003 and based in Pleasanton, California, the company is led by veterans from the semiconductor and high-tech industries. For more information about Pivotal, please visit www.pivotalsys.com, or send an email to info@pivotalsys.com.